



Attorney Docket :  
33082 M 119

**RESPONSE UNDER 37 CFR §1.116  
EXPEDITED PROCEDURE REQUESTED  
GROUP 2822**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

**CONFIRMATION NO.: 4442**

In re Applicants: Hitoshi KATO, et al.

Serial No. : 10/066,627

Filed : February 6, 2002

Art Unit : 2822

Examiner : Maria F. Guerrero

For : PRECLEANING METHOD OF PRECLEANING A SILICON  
NITRIDE FILM FORMING SYSTEM (AS AMENDED)

**AMENDMENT IN RESPONSE TO FINAL REJECTION**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed April 26, 2004, please amend the above-identified application as set forth below and consider the following remarks.